

L Number	Hits	Search Text	DB	Time stamp
1	118	SOI with substrate and anneal\$ same silicide and second with anneal\$	USPAT	2004/11/14 19:17
2	1	("0000438").PN.	USPAT	2004/11/14 19:16
3	116	SOI with substrate and anneal\$ same silicide and second with anneal\$ and method	USPAT	2004/11/14 19:17
4	21	SOI with substrate and anneal\$ same silicide and second with anneal\$ and method and insulating with hole	USPAT	2004/11/14 19:21
5	1	("6624010").PN.	USPAT	2004/11/14 19:23
6	2	("6174806") or ("6423599").PN.	USPAT	2004/11/14 19:23